

19	0	(((((427/79,99,126.3) or (257/296,298,306,310) or (438/239,240)).CCLS.) (((427/255.23,255.25,255.28,255.31,255.32,255.36,255.7) or (118/726) or (117/88,89,93,104)).CCLS.) ((427/901).CCLS.)) and ((liquid or precursor or solution) with vaporizer) and (ALD or ALE or (atomic adj layer adj (deposit\$3 or epitax\$5))) and (puls\$5 near4 (427/255.23,255.25,255.28,255.31,255.32,255.36,255.7) or (118/726) or (117/88,89,93,104)).CCLS.) ((427/901).CCLS.)) and (puls\$5 near4 (BaSrTiO3 or BaSr(TiO.sub.3)) and ((4CVD or (vapor adj deposit\$3)) same ((liquid or precursor or solution) with vaporizer) and (puls\$4 or multistep or (multi adj step) or (multiple adj step)))	USPAT; US-PGPUB	2003/08/27 11:00
20	28	((427/255.23,255.25,255.28,255.31,255.32,255.36,255.7) or (118/726) or (117/88,89,93,104)).CCLS.) ((427/901).CCLS.)) and (puls\$5 near4 (BaSrTiO3 or BaSr(TiO.sub.3)) and ((4CVD or (vapor adj deposit\$3)) same ((liquid or precursor or solution) with vaporizer) and (puls\$4 or multistep or (multi adj step) or (multiple adj step)))	USPAT; US-PGPUB	2003/08/27 11:07
21	19	((427/255.23,255.25,255.28,255.31,255.32,255.36,255.7) or (118/726) or (117/88,89,93,104)).CCLS.) ((427/901).CCLS.)) and (puls\$5 near4 (BaSrTiO3 or BaSr(TiO.sub.3)) and ((4CVD or (vapor adj deposit\$3)) same ((liquid or precursor or solution) with vaporizer) and (puls\$4 or multistep or (multi adj step) or (multiple adj step)))	USPAT; US-PGPUB	2003/08/27 10:51
22	53	((BST or (barium near2 strontium near2 titan\$4) or "BaSrTiO.sub.3" or BaSrTiO3 or "BaSr(TiO.sub.3)") same (ALD or ALE or (atomic adj layer adj deposit\$3)))	USPAT; US-PGPUB	2003/08/27 10:51
23	53	((BST or (barium near2 strontium near2 titan\$4) or "BaSrTiO.sub.3" or BaSrTiO3 or "BaSr(TiO.sub.3)") and ((4CVD or (vapor adj deposit\$3)) same ((liquid or precursor or solution) with vaporizer)) and (puls\$4 or multistep or (multi adj step) or (multiple adj step)))	USPAT; US-PGPUB	2003/08/27 10:58
24	28	((BST or (barium near2 strontium near2 titan\$4) or "BaSrTiO.sub.3" or BaSrTiO3 or "BaSr(TiO.sub.3)") and ((4CVD or (vapor adj deposit\$3)) same ((liquid or precursor or solution) with vaporizer)) and (puls\$4 or multistep or (multi adj step) or (multiple adj step))) not (((427/79,99,126.3) or (257/296,298,306,310) or (438/239,240)).CCLS.) (((427/255.23,255.25,255.28,255.31,255.32,255.36,255.7) or (118/726) or (117/88,89,93,104)).CCLS.) ((427/901).CCLS.)) and (BST or (barium near2 strontium near2 titan\$4) or "BaSrTiO.sub.3" or BaSrTiO3 or "BaSr(TiO.sub.3)) and ((4CVD or (vapor adj deposit\$3)) same ((liquid or precursor or solution) with vaporizer) and (puls\$4 or multistep or (multi adj step) or (multiple adj step)))	USPAT; US-PGPUB	2003/08/27 10:58
25	5	"BaSrTiO3.embryonic and of \$6VDtōen\vapōm adpdepōst\$8 withsā\$6CVDlōquAdDoorpA\$6Euorōor oatemutadp) lāyēh adpofdepōc\$itā\$do\$itpuls\$4 epimak\$5steprofva\$oltmeadp depp\$it\$3) (mumtpple\$8\$adj step))	USPAT; US-PGPUB	2003/08/27 11:06
26	280	(puls\$5 near4 (solution or liquid) near4 (\$4CVD or (vapor near2 deposit\$3)))	USPAT; US-PGPUB	2003/08/27 11:01
27	4	(DRAM or (dynamic adj random adj access adj memor\$3)) and (BST or (barium near2 strontium near2 titan\$4) or "BaSrTiO.sub.3" or BaSrTiO3 or "BaSr(TiO.sub.3)") and ((4CVD or (vapor adj deposit\$3)) and ((liquid or precursor or solution) with vaporiz\$5))	EPO; JPO; DERWENT; IBM_TDB	2003/08/27 11:03
28	14	(DRAM or (dynamic adj random adj access adj memor\$3)) and (BST or (barium near2 strontium near2 titan\$4) or "BaSrTiO.sub.3" or BaSrTiO3 or "BaSr(TiO.sub.3)") and ((4CVD or (vapor adj deposit\$3)) and (liquid or precursor or solution))	EPO; JPO; DERWENT; IBM_TDB	2003/08/27 11:05

29	10	((DRAM or (dynamic adj random adj access adj memor\$3)) and (BST or (barium near2 strontium near2 titan\$4) or "BaSrTiO.sub.3" or BaSrTiO3 or "BaSr(TiO.sub.3)") and ((\$4CVD or (vapor adj deposit\$3)) and (liquid or precursor or solution))) not ((DRAM or (dynamic adj random adj access adj memor\$3)) and (BST or (barium near2 strontium near2 titan\$4) or "BaSrTiO.sub.3" or BaSrTiO3 or "BaSr(TiO.sub.3)") and ((\$4CVD or (vapor adj deposit\$3)) and (liquid or precursor or solution) with vaporiz\$5)))	EPO; JPO; DERWENT; IBM_TDB	2003/08/27 11:03
30	5	(BST or (barium near2 strontium near2 titan\$4) or "BaSrTiO.sub.3" or BaSrTiO3 or "BaSr(TiO.sub.3)") and (ALD or ALE or (atomic adj layer adj (deposit\$3 or epitax\$6)))	EPO; JPO; DERWENT; IBM_TDB	2003/08/27 11:06
31	3	((liquid or precursor or solution) with (vaporiz\$6) with (\$4CVD or ALD or ALE or (atomic adj layer adj (deposit\$3 or epitax\$5)) or (vapor near2 deposit\$3)) with puls\$3)	EPO; JPO; DERWENT; IBM_TDB	2003/08/27 11:07
32	4	(puls\$5 near4 (solution or liquid) near4 (\$4CVD or (vapor near2 deposit\$3)))	EPO; JPO; DERWENT; IBM_TDB	2003/08/27 11:07
33	4	((puls\$5 near4 (solution or liquid) near4 (\$4CVD or (vapor near2 deposit\$3))) not ((liquid or precursor or solution) with (vaporiz\$6) with (\$4CVD or ALD or ALE or (atomic adj layer adj (deposit\$3 or epitax\$5)) or (vapor near2 deposit\$3)) with puls\$3))	EPO; JPO; DERWENT; IBM_TDB	2003/08/27 11:08
-	146	(DRAM adj capacitor).clm.	USPAT; US-PGPUB	2003/08/26 12:29
-	13847	6096134.pn. ot "20020197793"	USPAT; US-PGPUB	2003/08/26 12:30
-	2	6096134.pn. or "20020197793"	USPAT; US-PGPUB	2003/08/26 12:35
-	1	6258170.pn.	USPAT; US-PGPUB	2003/08/26 12:45
-	338	(Kher.in. or Wang.in. or Zhao.in. or (Applied adj Materials).as.) and (\$4CVD or (vapor adj deposit\$3)) and (liquid near2 (precursor or delivery or \$4CVD or (vapor near2 deposit\$3)))	USPAT; US-PGPUB	2003/08/26 12:51
-	48	((Kher.in. or Wang.in. or Zhao.in. or (Applied adj Materials).as.) and (\$4CVD or (vapor adj deposit\$3)) and (liquid near2 (precursor or delivery or \$4CVD or (vapor near2 deposit\$3))) and (DRAM or BST or (barium adj strontium near2 tit\$8))	USPAT; US-PGPUB	2003/08/26 12:49
-	23	(Kher or Wang or Zhao or (Applied adj Materials)) and (\$4CVD or (vapor adj deposit\$3)) and (liquid near2 (precursor or delivery or \$4CVD or (vapor near2 deposit\$3)))	EPO; JPO; DERWENT; IBM_TDB	2003/08/26 12:55
-	4	(Kher or Wang or Zhao or (Applied adj Materials)) and (\$4CVD or (vapor adj deposit\$3)) and (BST or (barium near2 strontium))	EPO; JPO; DERWENT; IBM_TDB	2003/08/27 08:40